

Electron scattering: cross sections for plasma modeling

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플라즈마물성데이터센터
Data Center for Plasma Properties

NFRI, Gunsan, 03.12.2014

Electrical discharges

- Discharges:

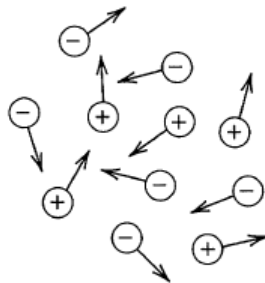
Are driven by voltage or current sources

Charged particle collisions with neutral particles are important

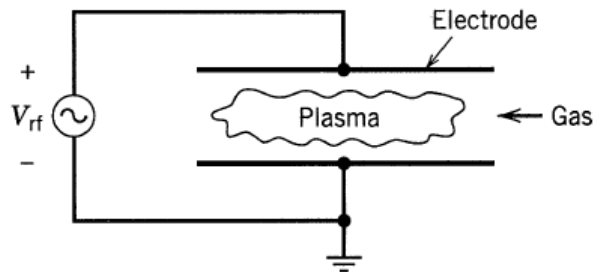
There are boundaries at which surface losses are important

Ionization of neutrals sustains the plasma in the steady state

The electrons are not in thermal equilibrium with the ions



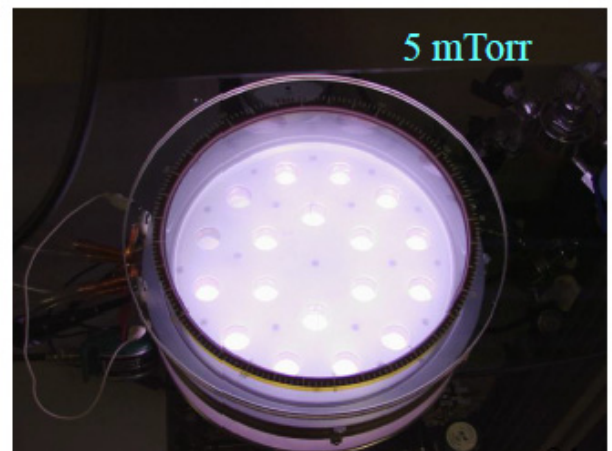
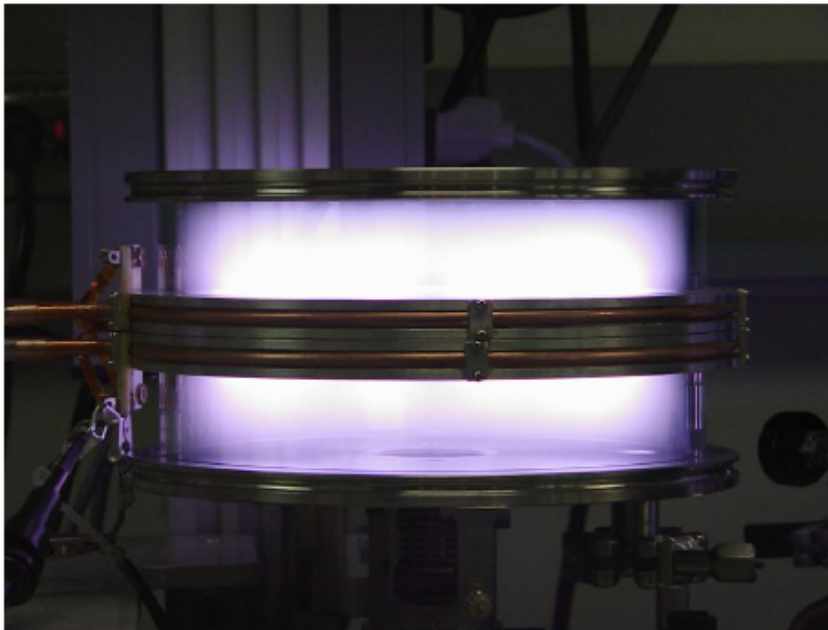
(a)



(b)

Plasma etching

Xenon, 400 kHz, 10 mTorr, 400 W



V. Godyak, PEUG, Santa Clara, 2003

other plasmas

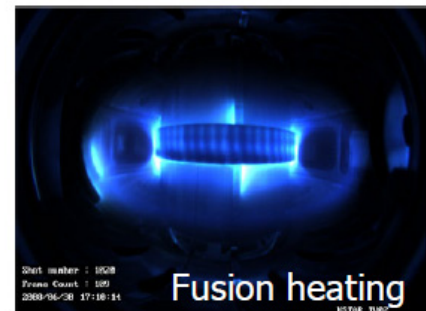
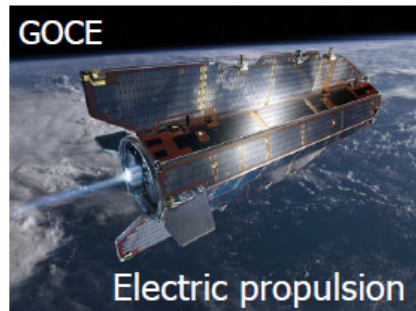
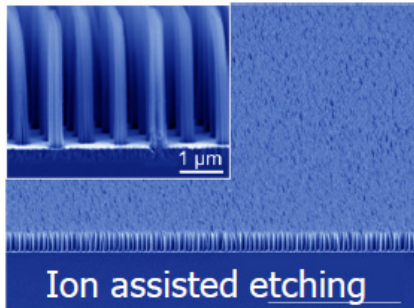
Ane Aanesland
Laboratoire de Physique des Plasmas
CNRS – Ecole Polytechnique
France

Electrons – Pros & Cons



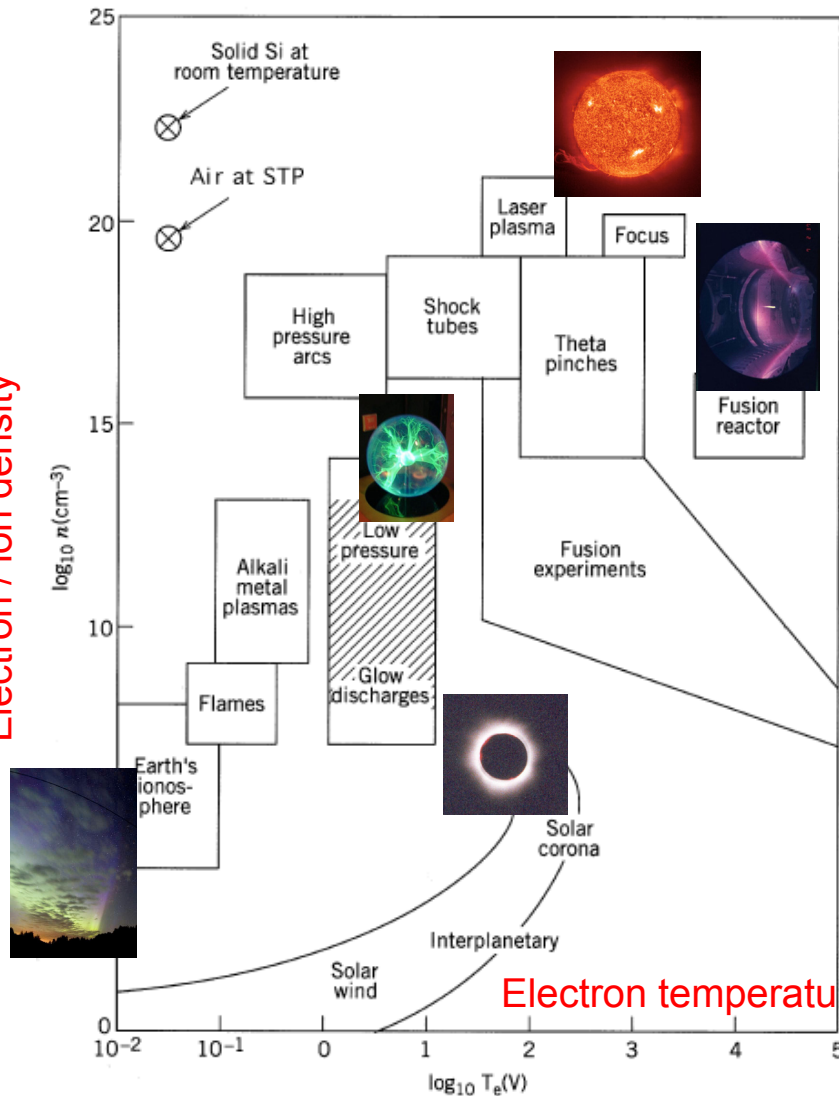
Electrons required for plasma **generation** and beam **neutralization**

Electrons cause problems by surface and differential **charging** and slow ion-electron **recombination**



„plasmas”

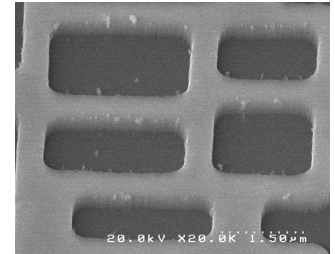
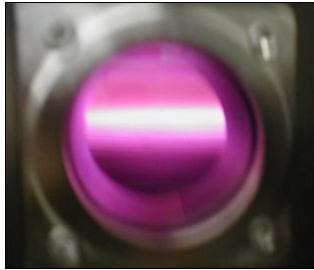
Electron / ion density



Electron temperature (i.e. electron mean energy)

Scheme: Michael A. Lieberman, 2003
Photo GK

Plasma etching

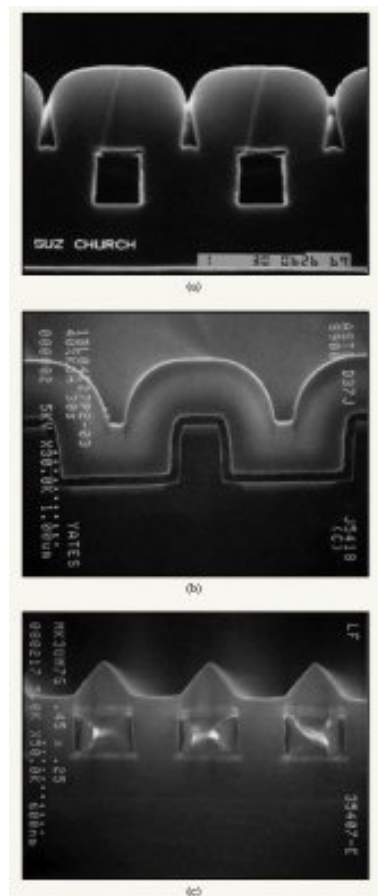


Material	Etch Gases	Reactive Species	By-product
Aluminum	Boron Trichloride and Chlorine	Free chlorine	AlCl ₃
Polyimide	Oxygen	Monatomic oxygen and/or ozone	CO and H ₂ O
Polysilicon	CF ₄ / 8% SF ₆ or Chlorine	Free fluorine or free chlorine	SiF ₄ or SiCl ₄
Silicon dioxide	Freon 14 and Freon 23	CF ₃	SiF ₄ and CO
Silicon nitride	Freon 14 (CF ₄) / 8% O ₂ or Sulfur Hexafluoride	Free fluorine	SiF ₄ and N ₂

Plasma deposition

Table 1 Typical electron-impact reactions of silane molecules in an rf plasma discharge. The asterisk (*) refers to electronic excited state. From [1].

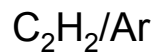
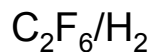
Reactant	Reaction products	Enthalpy of formation (eV)
$e^- + \text{SiH}_4 \rightarrow$	$\text{SiH}_2 + \text{H}_2 + e^-$	2.2
	$\text{SiH}_3 + \text{H} + e^-$	4.0
	$\text{Si} + 2\text{H}_2 + e^-$	4.2
	$\text{SiH} + \text{H}_2 + \text{H} + e^-$	5.7
	$\text{SiH}^* + \text{H}_2 + \text{H} + e^-$	8.9
	$\text{Si}^* + 2\text{H}_2 + e^-$	9.5
	$\text{SiH}_2 + 2\text{H}_2 + 2e^-$	11.9
	$\text{SiH}_3 + \text{H} + 2e^-$	12.3
	$\text{Si} + 2\text{H}_2 + 2e^-$	13.6
	$\text{SiH} + \text{H}_2 + \text{H} + 2e^-$	15.3



Plasma-assisted chemical vapor deposition of dielectric thin films for ULSI semiconductor circuits
D. R. Cote, S. V. Nguyen, A. K. Stamper, D. S. Armbrust, D. Tobben, R. A. Conti, and G. Y. Lee

IMB J. Res. Develop. 43, 1/2, 1999

Plasma deposition



Selected Applications

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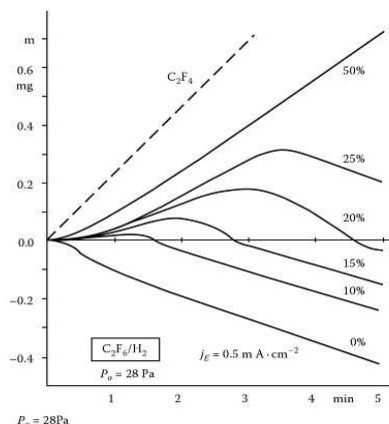


FIGURE 8.50 Polymer deposition and etching of Si measured on a Si substrate positioned on the powered electrode of a 50 kHz discharge in closed $\text{C}_2\text{F}_6/\text{H}_2$ discharges in relation to the discharge time for various H_2 admixtures ($p_0 = 28 \text{ Pa}$, $j = 0.5 \text{ mA}$).

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Nonthermal Plasma Chemistry and Physics

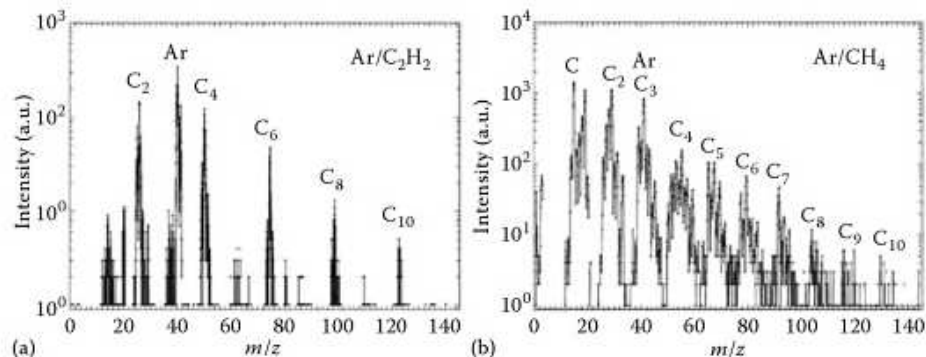
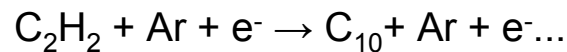
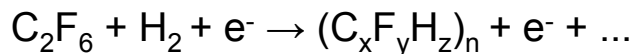


FIGURE 8.64 Ion mass spectra of $\text{Ar}/\text{C}_2\text{H}_2$ (a) and Ar/CH_4 (b) rf-discharges. (From Do, H.T. et al., *Contrib. Plasm. Phys.*, 45, 378, 2005.)



Modeling gas discharges

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Nonthermal Plasma Chemistry and Physics

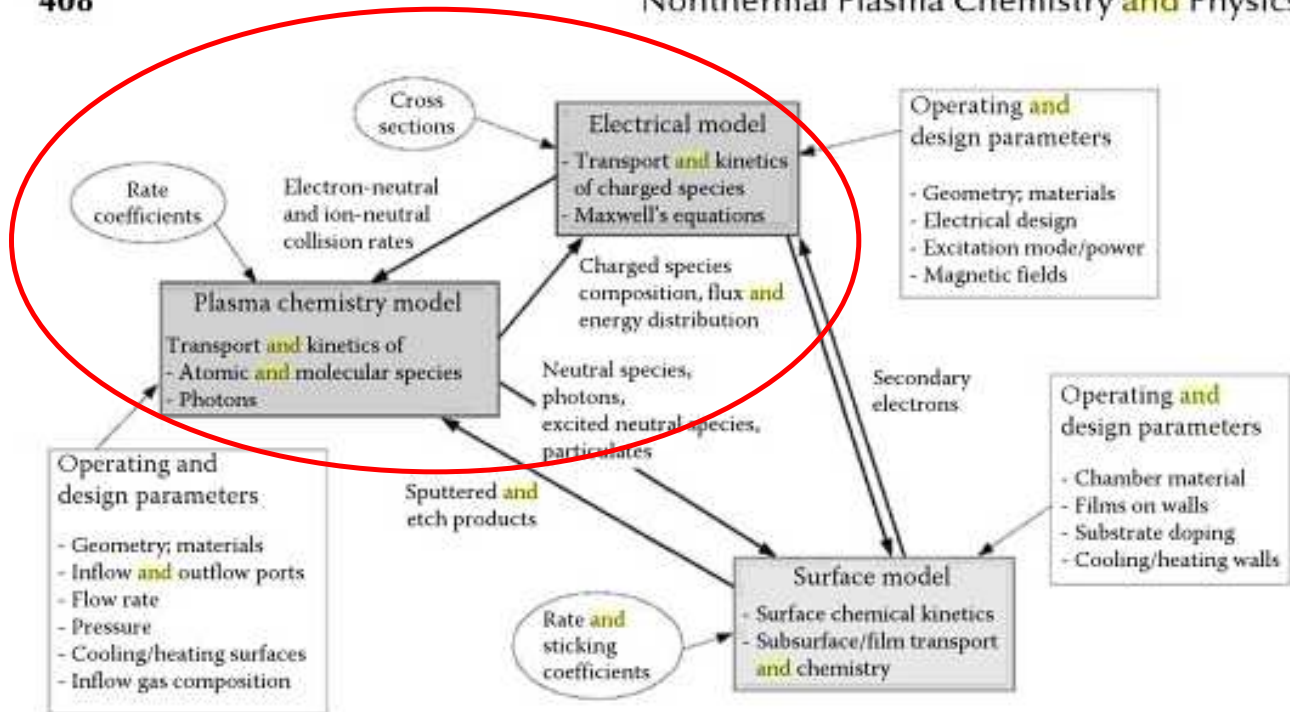


FIGURE 9.1 Components of plasma modeling. (From Graves, D.B., *IEEE Trans. Plasma Sci.*, 22, 31, 1994.)

1. Total cross section $I = I_0 \exp(-\sigma n l)$

2. Partial cross sections:

elastic scattering $e^- + A \rightarrow e^- + A$

rotational excitation $e^- + \text{CH}_4 (J=0) \rightarrow e^- + \text{CH}_4 (J=2)$

vibrational excitation $e^- + \text{AB} (v=0) \rightarrow e^- + \text{AB} (v>0)$

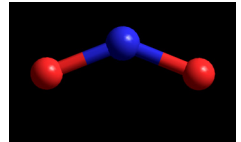
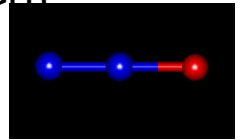
electron attachment (dissociative) $e^- + \text{AB} \rightarrow \text{A}^- + \text{B}$

electronic excitation $e^- + A \rightarrow e^- + A^*$

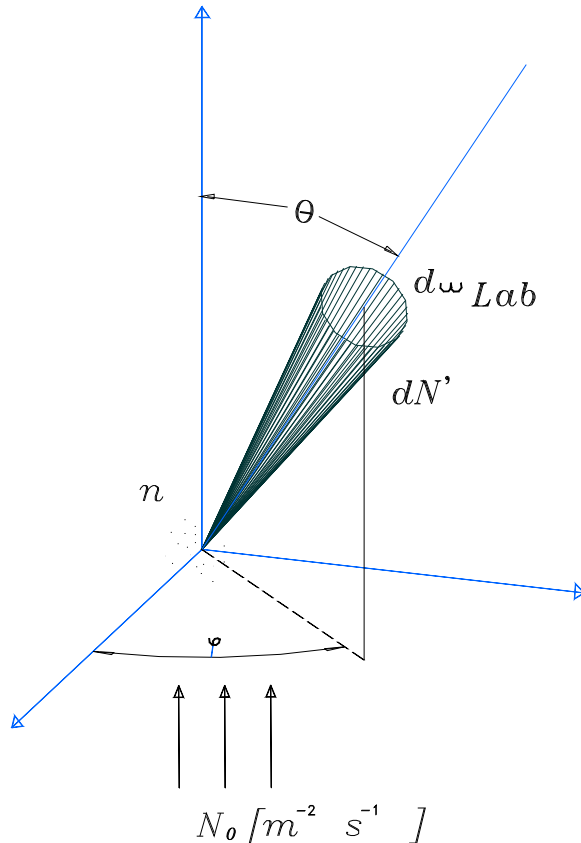
neutral dissociation $e^- + \text{AB} \rightarrow \text{A} + \text{B} + e^-$

ionization $e^- + A \rightarrow \text{A}^+ + 2e^-$

dissociative ionization $e^- + \text{AB} \rightarrow \text{A} + \text{B}^+ + 2e^-$



Definition: differential cross section



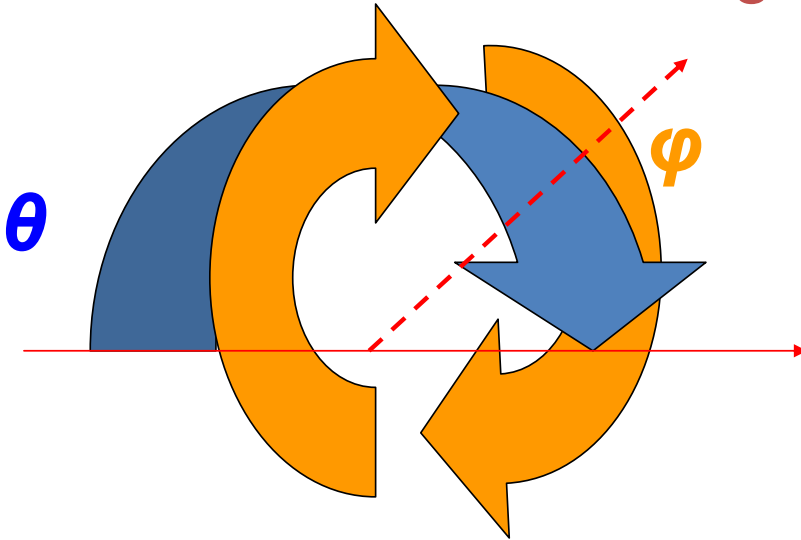
$$\frac{d\sigma}{d\omega} = \frac{dN'}{nN_0}$$

units

$$\left[\frac{N'}{nN_0} \right] = \frac{1/s/sr}{1/m^3} \frac{1}{1/(m^2s)} = 1/(m^2sr)$$

DCS = number of particles scattered into a given angle [in $1/(m^2sr)$]

Differential $\rightarrow$ integral cross section

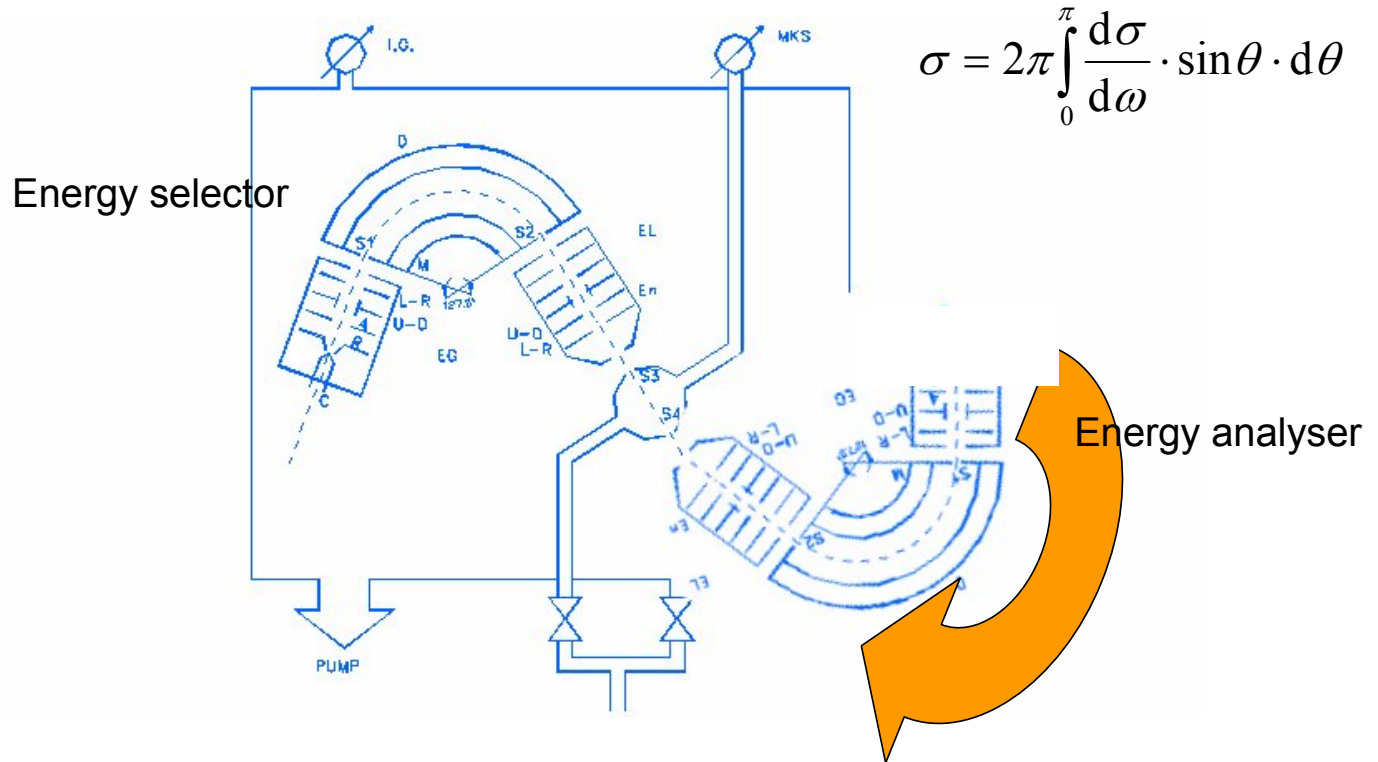


$$\sigma = \int_{4\pi} \frac{d\sigma}{d\omega} d\omega = \int_0^{2\pi} \int_0^{\pi} \frac{d\sigma}{d\omega} d\theta d\phi$$

cylindric symmetry:

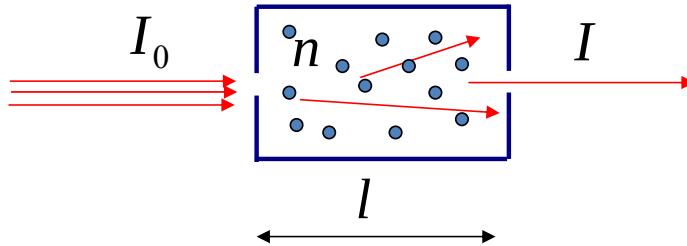
$$\sigma = 2\pi \int_0^{\pi} \frac{d\sigma}{d\omega} \cdot \sin\theta \cdot d\theta$$

Differential → integral cross sections



Measurements require normalization (we do not know n and N) !

Total cross section = attenuation of the beam



de Beer – Lambert law: $I = I_0 \exp(-\sigma n l)$

$$\sigma = -\frac{1}{n l} \ln \frac{I}{I_0}$$

We need to measure only: I, I_0, n, l
(n we get from ρ and T)

Total (absolute) measurements: I , I_0 , p , T , L

- declared errors: “**a few** per cent”

(1% pressure, 1% temperature, <1% scattering path)

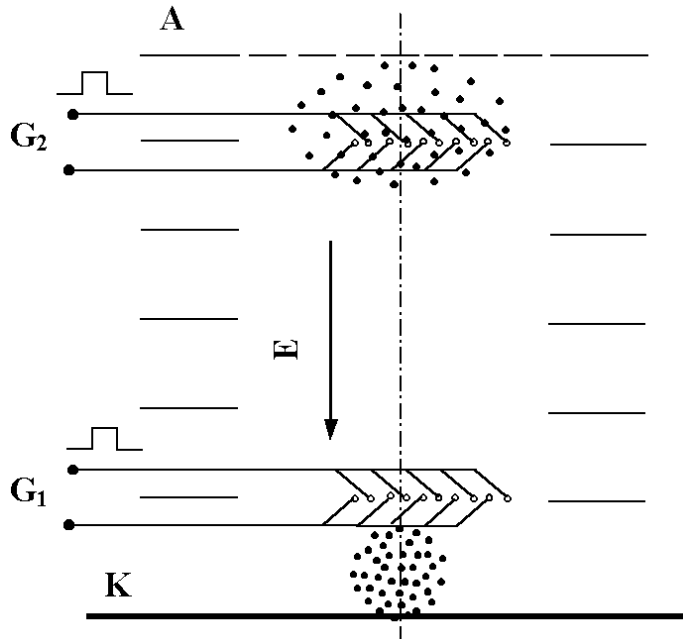
other errors: “a few more per cent”:

- energy resolution
- angular acceptance
- inelastic scattering discrimination
- normalizations (e.g. scattering path length)
- current stability and/or intensity

Electron-drift measurements

→ momentum transfer cross sections

$$\frac{\partial}{\partial t} n_e(\mathbf{r}, t) = -w \frac{\partial}{\partial z} n_e(\mathbf{r}, t) + D_T \left[\frac{\partial^2}{\partial x^2} n_e(\mathbf{r}, t) + \frac{\partial^2}{\partial y^2} n_e(\mathbf{r}, t) \right] + D_L \frac{\partial^2}{\partial z^2} n_e(\mathbf{r}, t)$$



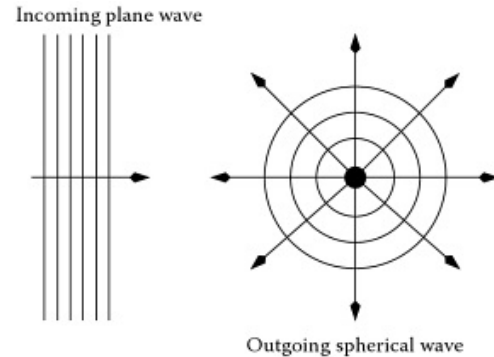
$$w = - \left(\frac{2}{m} \right)^{1/2} \frac{eF}{3N} \int_0^{\infty} \frac{E}{\sigma_m(E)} \frac{df_0(E)}{dE} dE$$

$$D_T = \left(\frac{2}{m} \right)^{1/2} \frac{1}{3N} \int_0^{\infty} \frac{E}{\sigma_m(E)} f_0(E) dE$$

Electron – atom scattering theory

$$\Phi = e^{ikz} + \frac{f(\theta)}{r} e^{ikr}$$

$$\frac{d\sigma}{d\omega} = |f(\theta)|^2$$



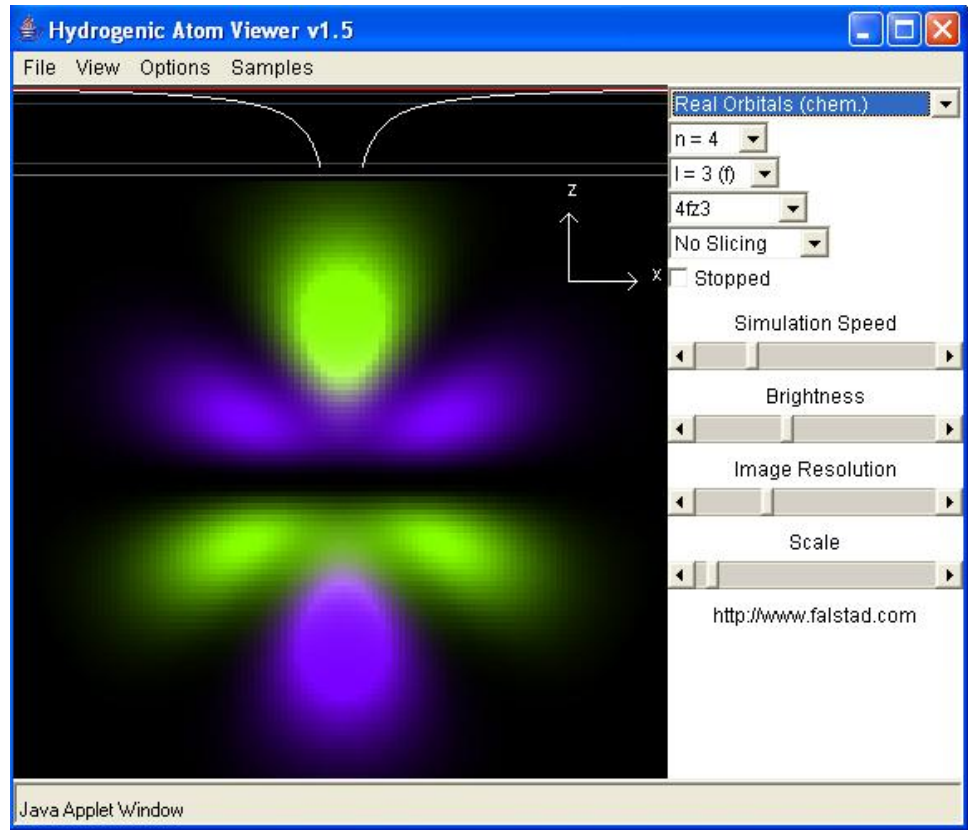
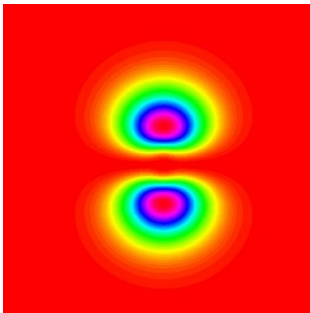
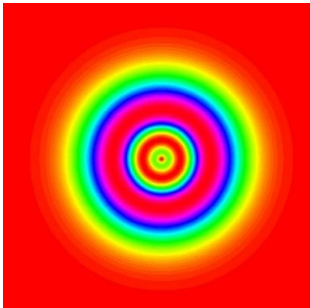
„Partial waves”, i.e. with different orbital momentum L : s , p , d etc.

$$f(\theta) = \frac{1}{2ik} \sum_{l=0}^{\infty} (2l+1) [\exp(2i\delta_l) - 1] \cdot P_l(\cos \theta)$$

$$\sigma = \frac{4\pi}{k^2} \sum_{l=0}^{\infty} (2l+1) \cdot \sin^2 \delta_l$$

orbitals s , p , d etc.

- $P_l(\cos\theta)$ are the same „spherical harmonic functions” that appear in atomic hydrogen orbitals, like f -orbital shown here



Electron – atom (elementary) scattering theory

$$\frac{d\sigma}{d\omega} = |f(\theta)|^2$$

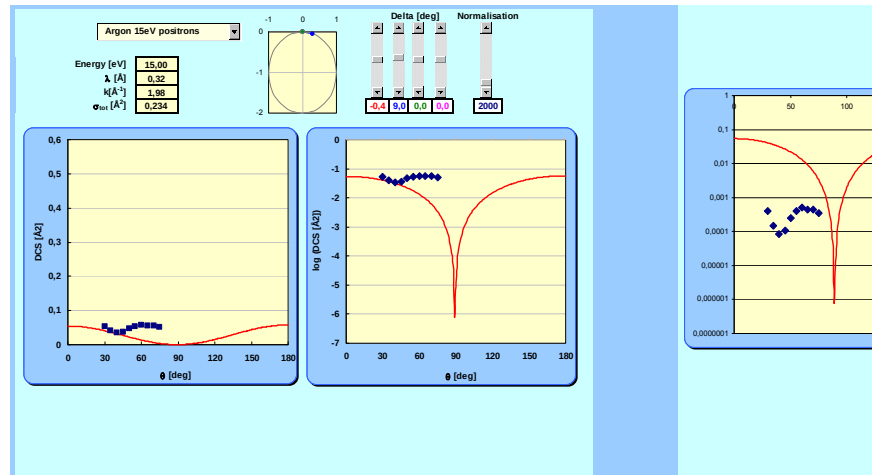
$$f(\theta) = \frac{1}{2ik} \sum_{l=0}^{\infty} (2l+1) [\exp(2i\delta_l) - 1] \cdot P_l(\cos\theta)$$

$$\frac{d\sigma}{d\theta}(\theta) \propto [P_l(\cos\theta)]^2$$

$$[P_0(\cos\theta)]^2 = 1$$

$$[P_1(\cos\theta)]^2 = (\cos\theta)^2$$

$$[P_1(\cos\theta)]^2 = \left[\frac{1}{2}(3\cos^2\theta - 1)\right]^2$$

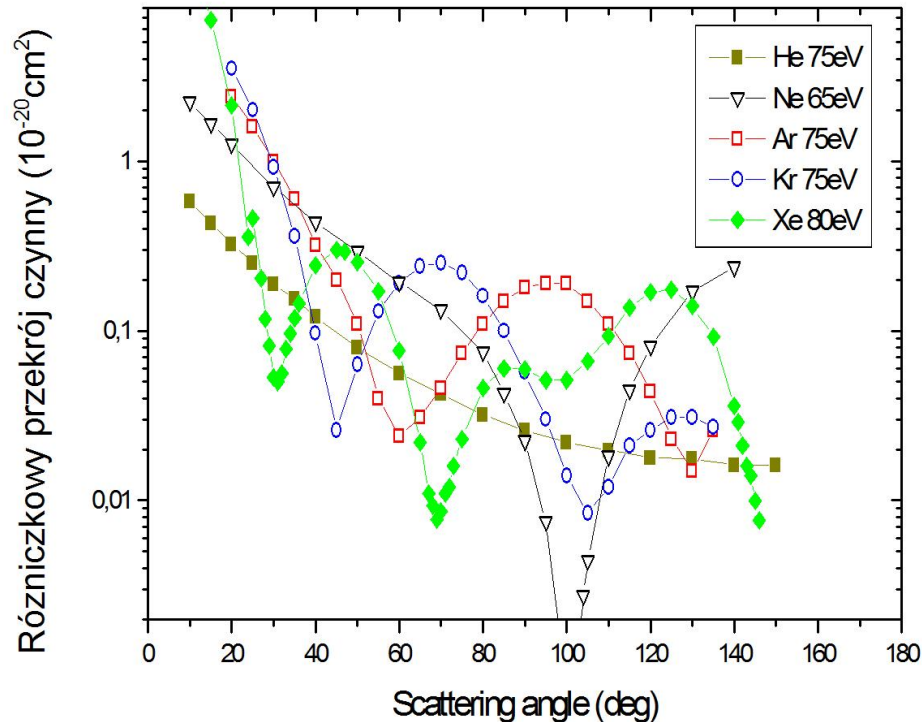


so, we can expect that DCS
are complicated functions of θ

H. Nowakowska

Electron – atom scattering experiment

$\sigma(\theta) \propto [P_l(\cos \theta)]^2$ we can expect that DCS are complicated functions of θ



Electron – atom scattering experiment

$\sigma(E) \propto \cdot \sum_l [P_l(\cos \theta, E)]^2$ we can expect that **ICS** are complicated functions of E

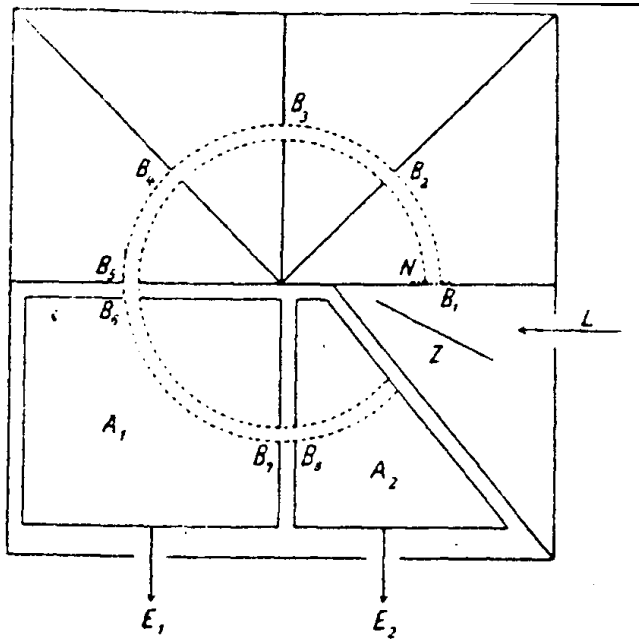
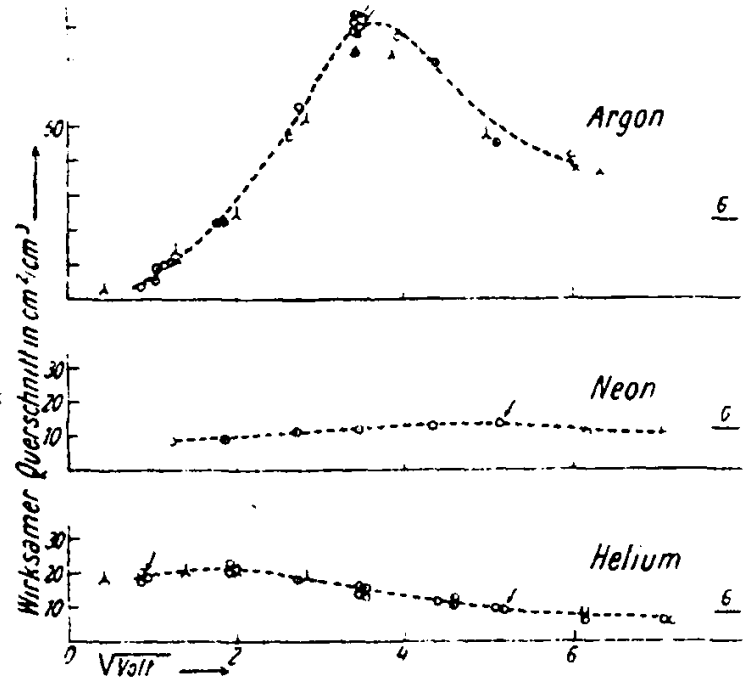
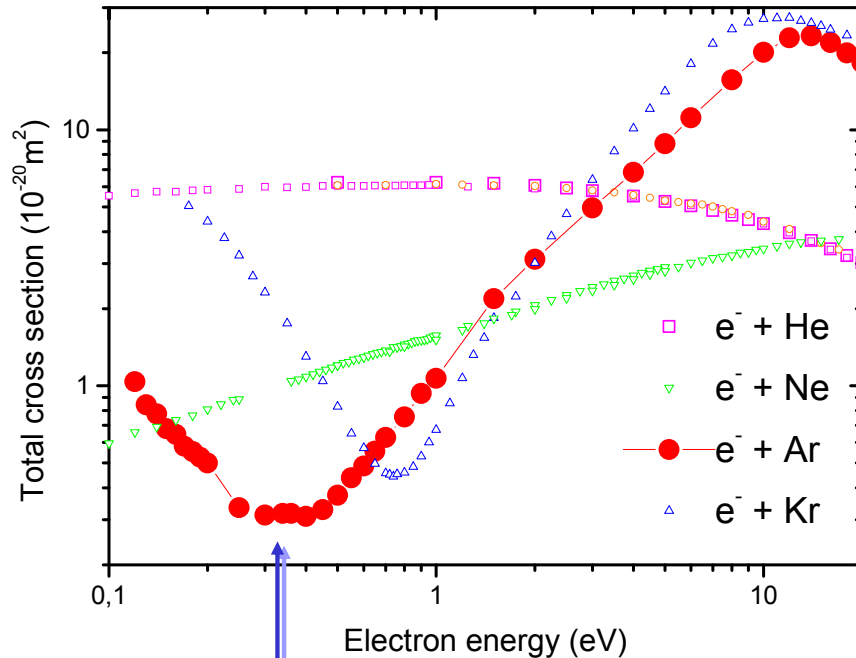


Fig. 1.

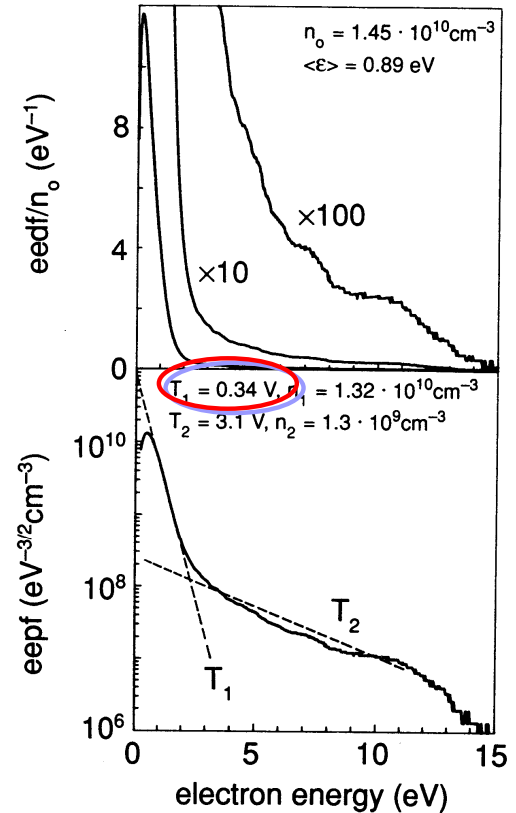


Carl Ramsauer, Gdansk, 1921

Plasma temperature ← integral cross sections

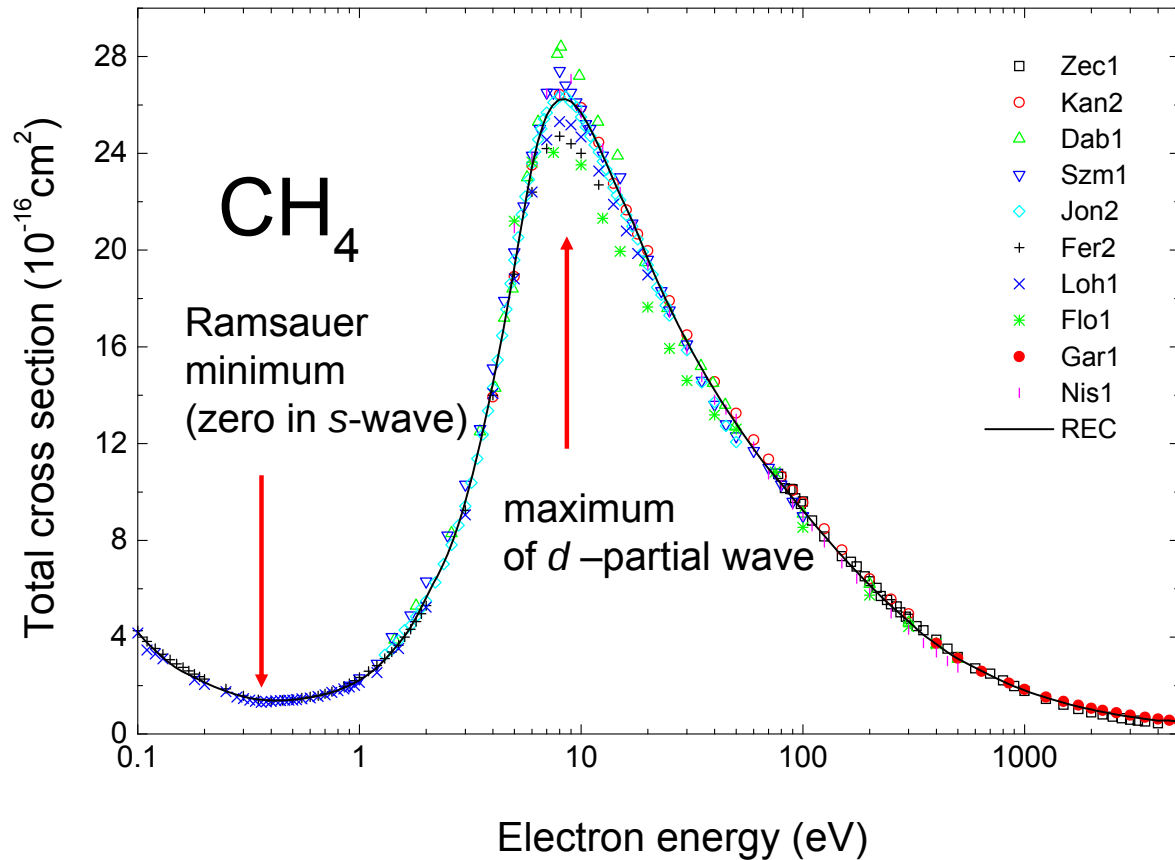


Ramsauer
minimum
(zero in s-wave)

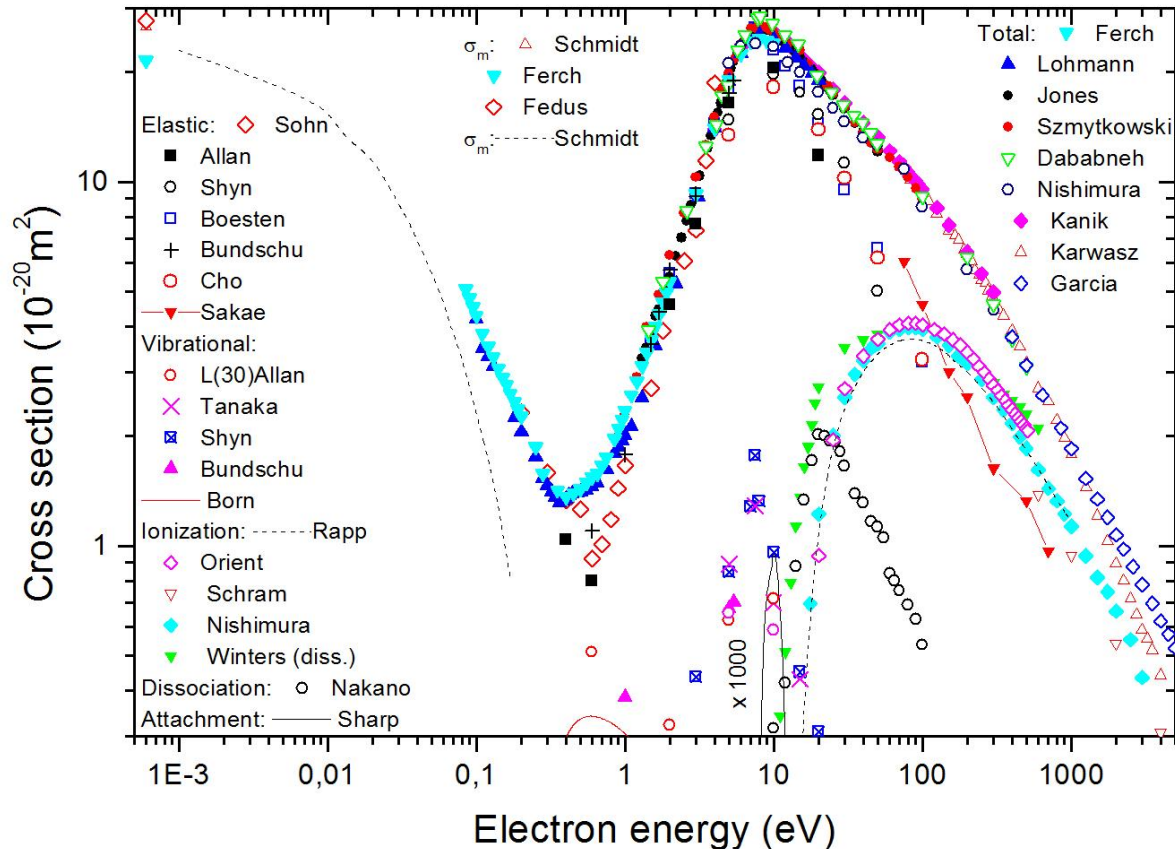


V. Godyak, Sendai 2006

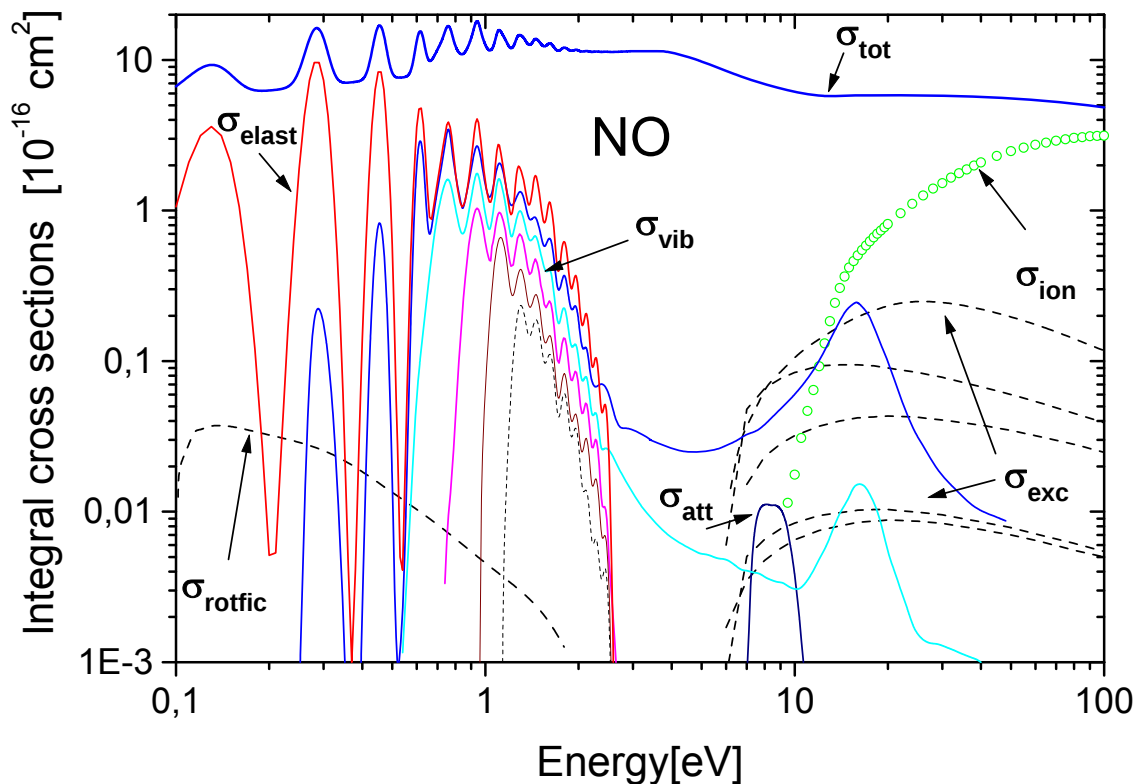
Total cross section: CH₄



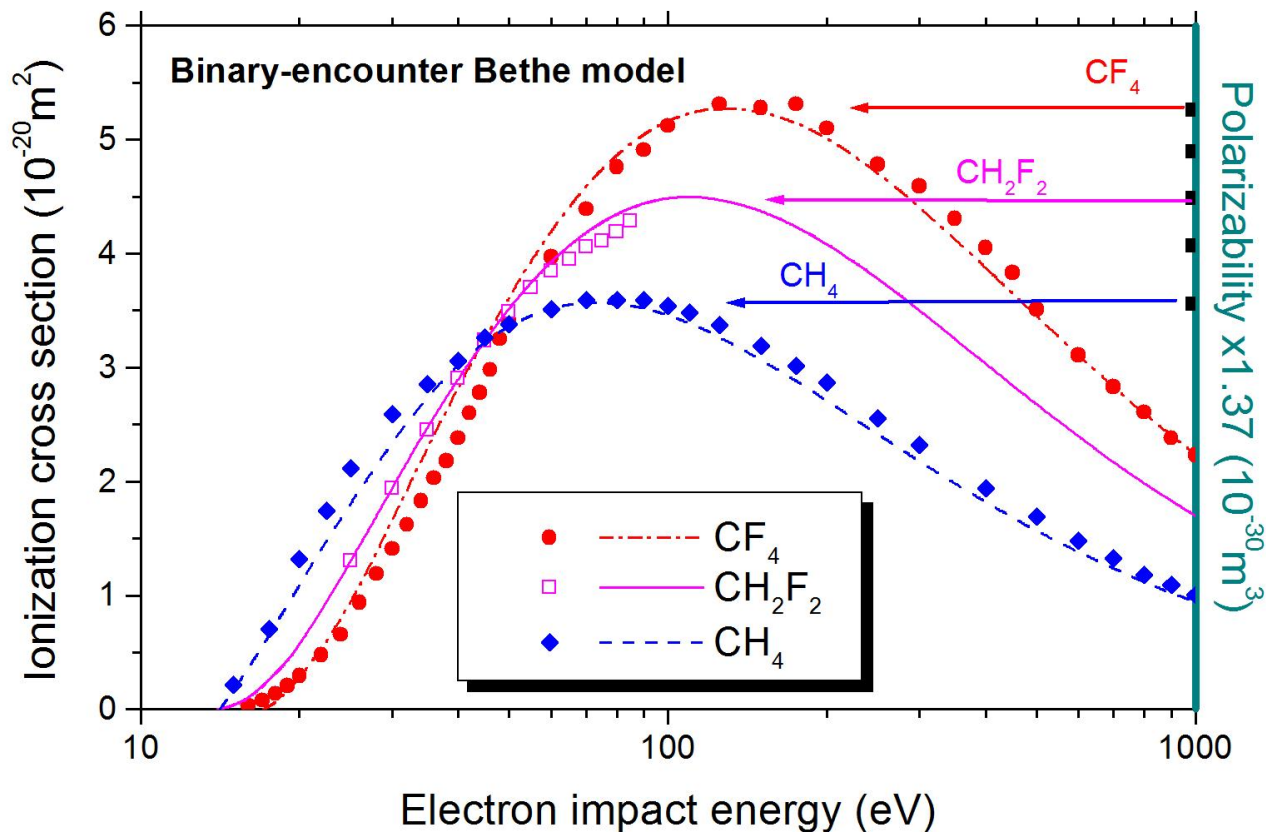
Integral cross sections for CH₄



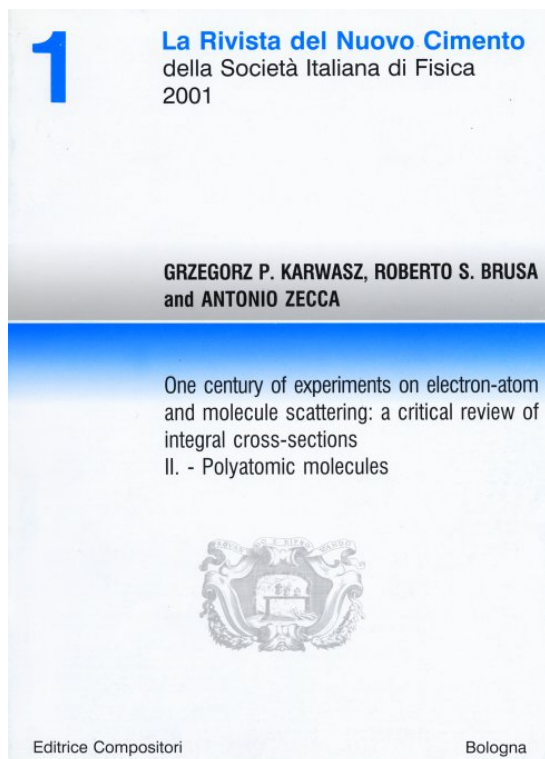
NO – overlapping resonances



Ionization – experiment and models



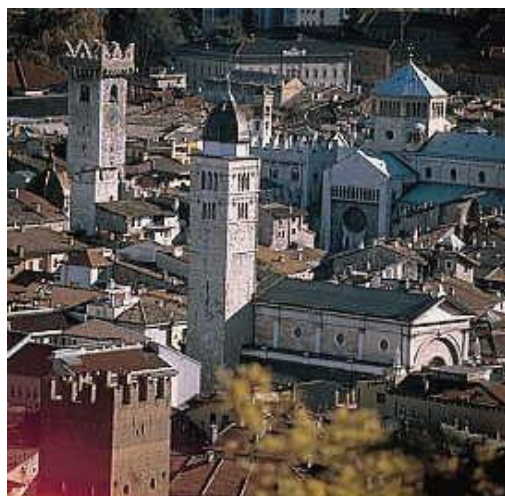
Reviews, experiments, theories...



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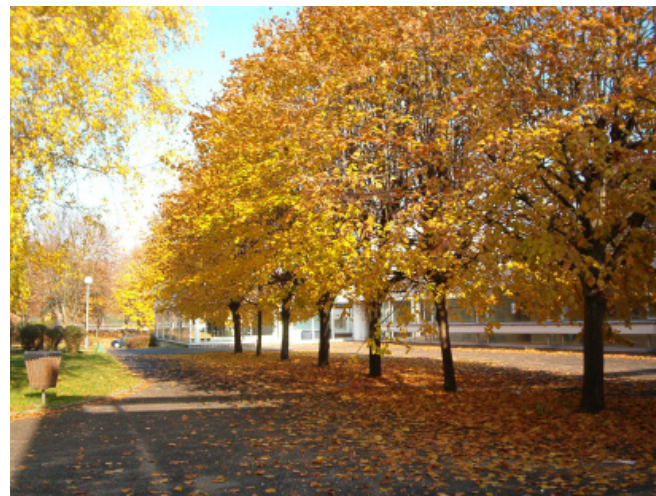
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Data Center for Plasma Properties



Trento



Berlin



Słupsk



Toruń, town of Copernicus

